

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An exposure apparatus that exposes a substrate via a liquid, comprising:

a nozzle member having at least any one of a supply outlet that supplies ~~the-a~~ liquid and a collection inlet that collects ~~the-a~~ liquid; and

a vibration isolating mechanism that supports the nozzle member and vibrationally isolates the nozzle member from a prescribed support member.

2. (Original) An exposure apparatus as recited in Claim 1, comprising:

an optical system;

wherein, the optical system is supported by the support member.

3. (Original) An exposure apparatus as recited in Claim 2,

wherein the vibration isolating mechanism performs vibrational isolation so that the vibrations of the nozzle member do not transmit to the optical system.

4. (Currently Amended) An exposure apparatus as recited in Claim 2-~~or 3~~,

wherein the nozzle member is annularly formed so that the nozzle member surrounds the optical system; and the nozzle member and the optical system are separately supported.

5. (Currently Amended) An exposure apparatus as recited in ~~any one claim of Claims 1 to 4~~ Claim 1,

wherein the vibration isolating mechanism comprises an active vibration isolating mechanism that dynamically vibrationally isolates the nozzle member from the support member.

6. (Currently Amended) An exposure apparatus as recited in ~~any one claim of Claims 1 to 5~~ Claim 1,

wherein the vibration isolating mechanism comprises a drive apparatus that drives the nozzle member with respect to the support member.

7. (Original) An exposure apparatus as recited in Claim 6,

wherein the drive apparatus can drive the nozzle member in relation to the directions of six degrees of freedom.

8. (Currently Amended) An exposure apparatus as recited in Claim 6-~~or 7~~, comprising:

a position measuring instrument that measures a positional relationship between the support member and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

9. (Currently Amended) An exposure apparatus as recited in Claim 6-~~or 7~~, comprising:

a position measuring instrument that measures a positional relationship between an optical system supported by the support member, and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

10. (Currently Amended) An exposure apparatus as recited in ~~any one claim of Claims 6 to 9~~ Claim 6, comprising:

an accelerometer that measures acceleration information of the nozzle member;
wherein, the drive apparatus drives based on a measurement result of the
accelerometer.

11. (Currently Amended) An exposure apparatus as recited in ~~any one claim of Claims 1 to 10~~ Claim 1,

wherein the vibration isolating mechanism comprises a passive vibration isolating
mechanism that passively vibrationally isolates the nozzle member from the support member.

12. (Currently Amended) An exposure apparatus that exposes a substrate via a liquid,
comprising:

a nozzle member comprising at least any one of a supply outlet that supplies ~~the-a~~
liquid and a collection inlet that collects ~~the-a~~ liquid;
a support member that supports the nozzle member; and
an adjustment mechanism that adjusts a positional relationship between the support
member and the nozzle member.

13. (Original) An exposure apparatus as recited in Claim 12,

wherein the adjustment mechanism comprises a drive apparatus that drives the nozzle
member with respect to the support member.

14. (Original) An exposure apparatus as recited in Claim 13, comprising:

a position measuring instrument that measures the positional relationship between the support member and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

15. (Currently Amended) An exposure apparatus as recited in ~~any one claim of Claims 12 to 14~~ Claim 12, comprising:

an optical system;

wherein, the optical system is supported by the support member.

16. (Currently Amended) An exposure apparatus that exposes a substrate via an optical system and a liquid, comprising:

a nozzle member supported by a prescribed support member, and comprising at least any one of a supply outlet that supplies ~~the-a~~ liquid and a collection inlet that collects ~~the-a~~ liquid; and

an adjustment mechanism that adjusts a positional relationship between the optical system and the nozzle member.

17. (Original) An exposure apparatus as recited in Claim 16,

wherein the optical system is supported by the support member; and the adjustment mechanism comprises a drive apparatus that drives the nozzle member with respect to the support member.

18. (Original) An exposure apparatus as recited in Claim 17, comprising:

a position measuring instrument that measures the positional relationship between the optical system and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

19. (Currently Amended) An exposure apparatus that exposes a substrate via a liquid, comprising:

a nozzle member supported by a prescribed support member, and comprising at least any one of a supply outlet that supplies ~~the-a~~ liquid and a collection inlet that collects ~~the-a~~ liquid;

a substrate stage that holds the substrate; and

an adjustment mechanism that comprises a drive apparatus that drives the nozzle member with respect to the support member, and that adjusts a positional relationship between the substrate stage and the nozzle member.

20. (Original) An exposure apparatus as recited in Claim 19, comprising:

a position measuring instrument that measures the positional relationship between the substrate stage and the nozzle member;

wherein, the drive apparatus drives based on a measurement result of the position measuring instrument.

21. (Currently Amended) An exposure apparatus that exposes a substrate via a liquid, comprising:

a nozzle member that comprises at least any one of a supply outlet that supplies ~~the-a~~ liquid and a collection inlet that collects ~~the-a~~ liquid;

wherein, at least one part of the nozzle member is movable in an optical axis direction of an exposure light that exposes the substrate.

22. (Original) An exposure apparatus as recited in Claim 21, comprising:
at least one position measuring instrument that detects information related to a position of the nozzle member;
wherein, the position of the nozzle member is controlled based on a measurement result of the position measuring instrument.

23. (Original) An exposure apparatus as recited in Claim 22,
wherein the position of the nozzle member is controlled based on information related to the liquid.

24. (Currently Amended) A device fabrication method that includes a lithographic process,

wherein an exposure apparatus as recited in ~~any one claim of Claims 1 to 23~~ Claim 1 is used in the lithographic process.